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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1. (twice amended) An optical semiconductor device comprising:
 - a substrate;
- a semiconductor laser including a lower clad layer, an active layer, and an upper clad layer formed in this order on said substrate;
- an electroabsorptive modulator including said lower clad layer, a light absorption layer, and said upper clad layer formed in this order on said substrate; and
- a separation region provided between said semiconductor laser and said electroabsorptive modulator and including said lower clad layer, a wave guide layer, and said upper clad layer formed in this order on said substrate; and
- a channel from which said upper clad layer is removed, said channel being provided such that said channel surrounds said upper clad layer, said channel extending up to said side of said separation region, wherein

said upper clad layer extends from said semiconductor laser through said separation region to said electroabsorptive modulator,

said electroabsorptive modulator receives light generated from said semiconductor laser in a wave guide direction through the wave guide layer,

said semiconductor laser, separation region, and electroabsorptive modulator each has a side provided in parallel with the wave guide direction of the light, and

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said upper clad layer extends in a direction crossing the wave guide direction up to said side of said separation region.

- 2. (twice amended) The An optical semiconductor device according to claim 1, which further comprises comprising:
 - a substrate;
- a semiconductor laser including a lower clad layer, an active layer, and an upper clad layer formed in this order on said substrate;
- an electroabsorptive modulator including said lower clad layer, a light absorption layer, and said upper clad layer formed in this order on said substrate;
- a separation region provided between said semiconductor laser and said electroabsorptive modulator and including said lower clad layer, a wave guide layer, and said upper clad layer formed in this order on said substrate;
- a contact layer provided on said upper clad layer, <u>said</u> contact layer having a high resistance;
- a first upper electrode provided on said contact layer in said semiconductor laser[[,]]; and
- a second upper electrode provided on said contact layer in said electroabsorptive modulator, wherein
- said upper clad layer extends from said semiconductor laser through said separation region to said electroabsorptive modulator,

said electroabsorptive modulator receives light generated from said semiconductor laser in a wave guide direction through the wave guide layer,

said semiconductor laser, separation region, and
electroabsorptive modulator each has a side provided in
parallel with the wave guide direction of the light, and

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said upper clad layer extends in a direction crossing the wave guide direction up to said side of said separation region.

3. (previously presented) The optical semiconductor device according to claim 1, which further comprises a lower electrode provided on an under-side of said substrate.

4-5. (canceled)

- 6. (previously presented) The optical semiconductor device according to claim 1, wherein said upper clad layer extends from said semiconductor laser through said separation region to said electroabsorptive modulator via said each side.
- 7. (previously presented) The optical semiconductor device according to claim 2, wherein said contact layer is removed from said separation region.

8. (canceled)

- 9. (currently amended) The optical semiconductor device according to claim $\frac{8}{2}$, wherein said high resistance of said contact layer is made by ion-implantation.
- 10. (currently amended) An optical semiconductor device, comprising:
 - a substrate,
- a semiconductor laser formed on the substrate and including an active layer for generating a laser beam in a beam direction,

an electroabsorptive modulator formed on the substrate and including a light absorption layer for receiving the

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laser beam from the semiconductor laser to generate an electrical signal,

a separation region formed on the substrate between the semiconductor laser and the electroabsorptive modulator, said separation region having side portions extending in parallel to the beam direction, and

a slab disposed in the separation region for radiating heat, said slab extending continuously from one of the side portions to the other of the side portions in a direction crossing the beam direction, and

a channel disposed in the separation region around the slab and extending between the side portions of the separation region.

11. (canceled)

- 12. (previously presented) The optical semiconductor device according to claim 10, further comprising a side slab disposed outside at lease one of the side portions of the separation region and extending in the beam direction, said slab being connected to the side slab.
- 13. (previously presented) The optical semiconductor device according to claim 10, wherein said semiconductor laser and said electroabsorptive modulator include upper electrodes, respectively, said slab being connected to at least one of the upper electrodes.
- 14. (new) The optical semiconductor device according to claim 2, which further comprises a lower electrode provided on an under-side of said substrate.

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15. (new) The optical semiconductor device according to claim 2, wherein said upper clad layer extends from said semiconductor laser through said separation region to said electroabsorptive modulator via said each side.